



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

APPLICANT: Henry Windischmann

SERIAL NO.: 10/608,674

GROUP ART UNIT:

FILED: June 27, 2003

EXAMINER:

FOR: Corrosion and Erosion
resistant thin film diamond
coating and applications
therefor

ATT'Y DOCKET: NOR-DF-3869 D1

Honorable Commissioner for Patents
PO Box 1450
Alexandria, VA 22313-1450

I hereby certify that this correspondence is being deposited on
this day with the United States Postal Service as first class
mail in an envelope addressed to : Commissioner for Patents,
PO Box 1450, Alexandria, VA 22313-1450

David P. Gordon

David P. Gordon
Reg. No. 29,996

Nov 3, 2003
Date

Sir:

SUBMITTAL OF DOCUMENTS PURSUANT TO DUTY OF DISCLOSURE

Pursuant to applicant's duty of disclosure under 37 CFR Section 1.56, enclosed is a completed form PTO-1449 as well as copies of the cited documents which relate to the above-referenced patent application. Since this document submittal is being presented prior to the first examination on the merits, no fee is due herewith.

German Patent Number DE 196 03 093 A1 discloses a rod shaped electrode with a corrosion protection layer and the production process thereof.

Japanese patent publication No. 7-5304 discloses the manufacture of an optical window including both a diamond layer and an optical selection layer.

Japanese patent publication No. 7-45748 discloses diamond growth to 300 μm on a polycrystalline Si board using a heat filament CVD method.

Japanese patent publication No. 9-67195 discloses a method of producing diamond Crystalline using gaseous raw materials.

Japanese patent publication No. 10-96082 discloses the use of a carbon-based film to protect the inside surface of a substrate treating system.



The listed documents are brought to the Examiner's attention because they are known to the applicant and/or the applicant's attorney and may be considered by the Examiner to be material to his/her examination. This listing should not be construed as representation that a search has been made or that no better art exists. No inference should be made that the documents are in fact material merely because they are referenced herein. Moreover, no representation is made that the brief descriptions of the references herein necessarily describe the most material aspects of the references. Further, by this listing, the applicant is not making any admission regarding the relative dates of the invention and listed disclosures.

Respectfully submitted,

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INFORMATION DISCLOSURE CITATION

PAGE 1 OF 1

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Applicant
Henry Windischmann

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Group

US PATENT DOCUMENTS

Examiner Initials		Document No.	Date	Name	Class	Subclass	Filing date if approp.
	A	4,740,263	4/88	Imai et al.	156	613	
	B	5,146,481	9/92	Garg et al.	378	35	
	C	5,206,083	4/93	Raj et al.	428	323	
	D	5,217,700	6/93	Kurihara et al.	423	446	
	E	5,221,411	6/93	Narayan	156	603	
	F	5,225,926	7/93	Cuomo et al.	359	350	
	G	5,370,299	12/94	Tanabe et al.	228	176	
	H	5,406,081	4/95	Inushima	250	338.4	
	I	5,411,797	3/96	Davanloo et al.	428	336	
	J	5,420,443	5/95	Dreifus et al.	257	77	
	K	5,427,054	6/95	Saito et al.	117	88	
	L	5,496,596	3/96	Herb et al.	427	577	
	L	5,525,815	6/96	Einset	257	77	
	M	5,628,824	5/97	Vohra et al.	117	101	
	N	5,736,252	4/98	Bigelow et al	428	408	
	O	5,747,118	5/98	Bunshah et al.	427	577	
	P	5,851,658	12/98	Yamamoto et al.	428	334	
	Q	5,904,778	5/99	Lu et al.	118	723R	
	R	5,910,221	6/99	Wu	118	723R	
	S	5,952,060	9/99	Ravi	427	577	
	T	5,955,155	9/99	Yamamoto et al.	427	577	
	U	5,916,370	6/99	Chang	118	729	
	V	6,072,275	6/00	Kobashi	313	506	
	W	6,605,352	8/03	Windischmann	428	408	
	X						

EXAMINER

DATE CONSIDERED



INFORMATION DISCLOSURE CITATION PAGE 2 OF 2				Atty Docket No. NOR-DF-3869 D1		Serial No. 10/608,674		
				Applicant Henry Windischmann				
				Filed June 27, 2003		Group		
FOREIGN PATENT DOCUMENTS								
Examiner Initials		Document No.	Date	Country	Class	Sub- class	Translation	
							Yes	No
	2A	0 449 571 A	2/91	EPO	B23B	27/14		
	2B	0 635 584 A1	1/95	EPO	C23C	16/26		
	2C	0 714 997 A1	6/96	EPO	C23C	16/26		
	2D	19603093 A1	7/97	Germany	G01F	23/22		x
	2E	7-5304	4/93	Japan	G02B	5/00		
	2F	7-45748	2/95	Japan	H01L	23/14		
	2G	9-67195	11/97	Japan	C30B	29/04		
	2H	10-96082	4/98	Japan	C23C	16/44		
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)								
	AA	"Nucleation & growth of diamond films on single crystal and polycrystalline tungsten substrates"; <i>Elsevier Science Publishers</i> , vol. 9, no.3-6, April 2002 pp. 262-268						
	BB	"Nano-diamond films produced from CVD of camphor"; <i>Elsevier Science Publishers</i> , vol. 7, no. 6, June 1998, pp. 845-852						
	CC	"Diamond Growth with Boron Addition" by P. Hartmann, et al., <i>International Journal of Refractory Metals and Hard Materials</i> , Vol. 16, Issue 3, pp. 223-232, 1998						
	DD	"Ion Implantation in Predoped CVD Diamond" by H. Yagyu, et al., <i>Thin Solid Films</i> 281-282, 1996, pp. 271-274						
	EE	"Fabrication of Boron-doped CVD Diamond Microelectrodes" by J. Cooper et al., <i>Analytical Chemistry</i> , Vol 70, No. 3 February 1, 1998, pp. 464-467						
EXAMINER				DATE CONSIDERED				